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APPLICATION NO.	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/657,789 09/08/2003		09/08/2003	Yuan-Hsun Wu	10112881	1374	
34283	7590	12/27/2005		EXAMINER		
QUINTER			RUGGLES, JOHN S			
1617 BROADWAY, 3RD FLOOR SANTA MONICA, CA 90404				ART UNIT	PAPER NUMBER	
	,			1756		

DATE MAILED: 12/27/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

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CFR 1.121(d). PTO-152.	
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			Application	No.	Applicant(s)			
Office Action Summary			10/657,789		WU, YUAN-HSUN			
			Examiner		Art Unit			
			John Ruggle		1756			
Period fo	The MAILING DATE of this commun or Reply	nication app	ears on the c	over sheet with the c	orrespondence ad	ldress		
WHIC - Externafter - If NC - Failur Any	ORTENED STATUTORY PERIOD F CHEVER IS LONGER, FROM THE N Insions of time may be available under the provisions SIX (6) MONTHS from the mailing date of this common openiod for reply is specified above, the maximum some re to reply within the set or extended period for reply reply received by the Office later than three months and patent term adjustment. See 37 CFR 1.704(b).	MAILING DA s of 37 CFR 1.13 munication. tatutory period w y will, by statute,	ATE OF THIS 36(a). In no event, vill apply and will e , cause the applica	COMMUNICATION however, may a reply be tim xpire SIX (6) MONTHS from tion to become ABANDONEI	l. ely filed the mailing date of this c O (35 U.S.C. § 133).			
Status								
1)	Responsive to communication(s) file	ed on <i>08 Se</i>	eptember 200	03.				
2a)□	Responsive to communication(s) filed on <u>08 September 2003</u> . This action is FINAL . 2b) This action is non-final.							
3)		,—			secution as to the	e merits is		
-,	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.							
Dispositi	on of Claims							
4)⊠	Claim(s) 1-12 is/are pending in the	application.						
•	4a) Of the above claim(s) is/a			ideration.				
	Claim(s) <u>none</u> is/are allowed.		•					
· · ·	Claim(s) <u>2-6</u> is/are rejected.							
7)								
8)⊠	Claim(s) 1-12 are subject to restrict	ion and/or e	election requi	rement.				
Applicati	on Papers		•			•		
9)	The specification is objected to by the	ne Examiner	r. '					
10)	The drawing(s) filed on is/are	: a) acce	epted or b)	objected to by the E	xaminer.			
	Applicant may not request that any obje	ection to the o	drawing(s) be	held in abeyance. See	37 CFR 1.85(a).			
	Replacement drawing sheet(s) including	g the correcti	ion is required	if the drawing(s) is obj	ected to. See 37 Cl	FR 1.121(d).		
11)[The oath or declaration is objected t	o by the Ex	aminer. Note	the attached Office	Action or form P7	ΓΟ-152.		
Priority ι	ınder 35 U.S.C. § 119							
a)	Acknowledgment is made of a claim All b) Some * c) None of: 1. Certified copies of the priority 2. Certified copies of the priority 3. Copies of the certified copies application from the Internationsee the attached detailed Office actions	documents documents of the prior	s have been is have been i ity document i (PCT Rule	received. received in Applications s have been received 17.2(a)).	on No d in this National	Stage		
2)	t(s) e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (f nation Disclosure Statement(s) (PTO-1449 or r No(s)/Mail Date		5	Interview Summary Paper No(s)/Mail Da Notice of Informal Pa	te	D-152)		

DETAILED ACTION

Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112:

The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

Claims 2-6 each recite the limitation "The method as claimed in claim 1" in reference to the photomask structure of claim 1. There is insufficient antecedent basis for this limitation in each of claims 2-6, because claim 1 is not drawn to a method at all, but rather to a recited photomask structure; and also because each of claims 2-6 further limit the actual photomask structure. Therefore, for the purpose of this Office action and in order to advance the prosecution of this application, the above limitation in each of claims 2-6 has been interpreted as referring to the photomask structure recited by claim 1, on which each of claims 2-6 depend. For at least these reasons, the above limitation "The method as claimed in claim 1" in each of claims 2-6 has been interpreted to mean --The method photomask structure as claimed in claim 1--.

Election/Restrictions

Restriction to one of the following inventions is required under 35 U.S.C. 121:

- I. Claims 1-6, drawn to a photomask structure (photomask product in which claims2-6 have been interpreted as stated above), classified in class 430, subclass 5.
- II. Claims 7-12, drawn to a method of patterning a photoresist on a substrate (process of using a photomask product) and etching an array trench area in the substrate through the patterned photoresist, classified in class 430, subclass 313.

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Inventions 1 and II are related as a photomask product and a process of using a photomask product. The inventions can be shown to be distinct if either or both of the following can be shown: (1) the process for using the photomask product as claimed can be practiced with another materially different product or (2) the photomask product as claimed can be used in a materially different process of using that product (MPEP § 806.05(h)). In the instant case, the photomask product as claimed in Group I can be used in a materially different process of using that product than is claimed in Group II, such as a process of patterning a photoresist on a substrate and *coating* (*without* etching) the substrate through the patterned photoresist.

Because these inventions are distinct for the reasons given above and have acquired a separate status in the art as shown by their different classification and also because of their recognized divergent subject matter, restriction for examination purposes as indicated is proper.

Applicant is advised that the reply to this requirement to be complete must include an election of the invention to be examined even if the requirement is traversed (37 CFR 1.143).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to John Ruggles whose telephone number is 571-272-1390. The examiner can normally be reached on Monday-Thursday and alternate Fridays.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark Huff can be reached on 571-272-1385. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

John Ruggles Examiner

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MARK F. HUFF

SUPERVISORY PATENT EXAMINER TECHNOLOGY CENTER 1700